

Structure fabrication and assembly tolerances

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Tolerances of the structures

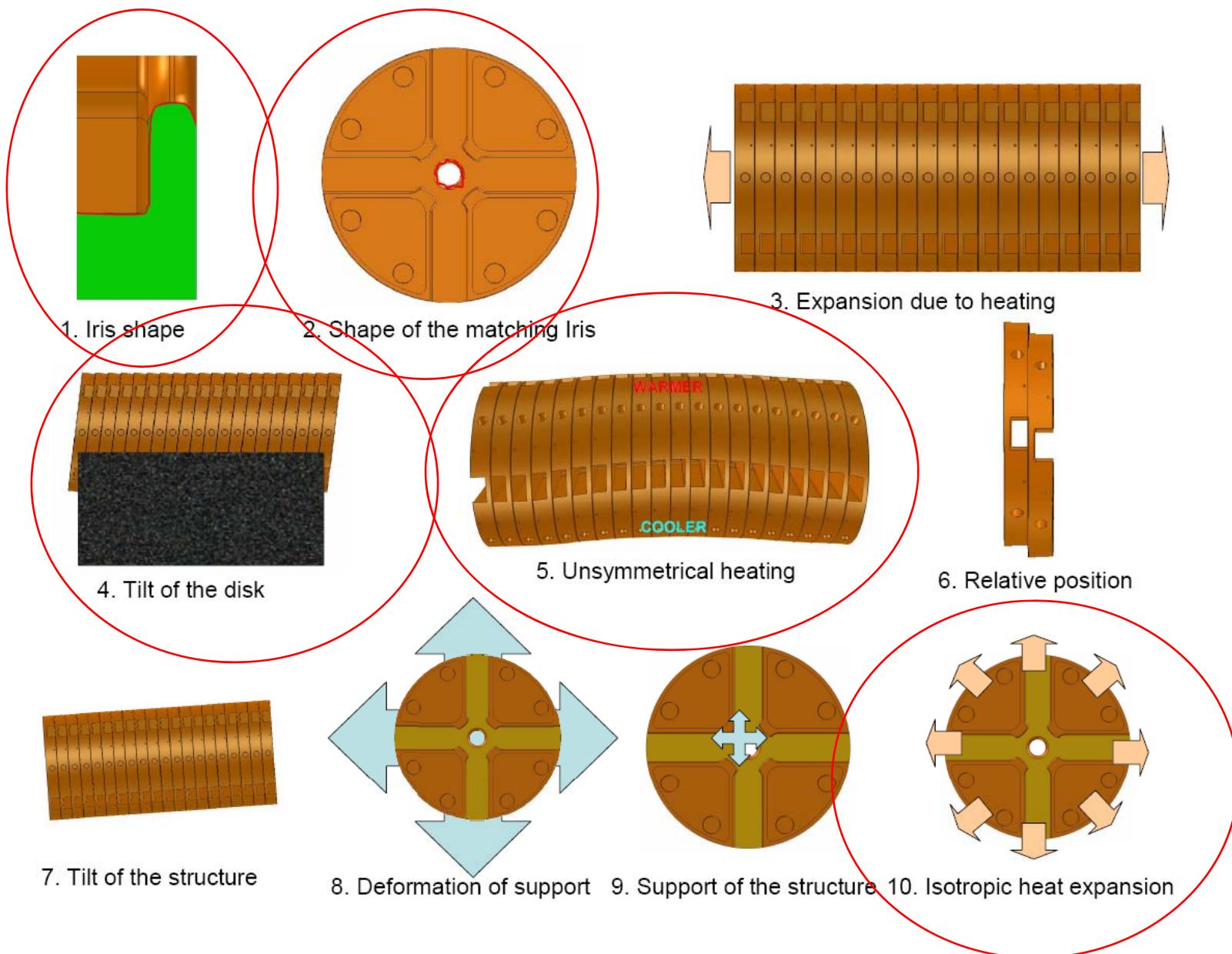
4 kinds of tolerances:

- *Machining ($\Delta x, \Delta y, \Delta z$)*
- *Assembly ($\Delta x, \Delta y, \Delta z$)*
- *Alignment ($\Delta x, \Delta y, \Delta z$)*
- *Operation [Cooling] ($\Delta T (t)$ water in, $\Delta T (z)$)*

4 kinds of problems:

- *Beam induced transverse kick (wakefield)*
- *RF induced transverse kick*
- *RF matching (reflected power)*
- *Phase error*

Item	Effect of the item	Performance	Cause				Solution	Magnitude of tolerance	Criticality	Comments	Scheme
			Mach.	Assem.	Align.	Oper.					
SHAPE											
Shape of an Iris	dephasing	lower efficiency	x				Tuning	± 0.001 mm	high	local	1
Shape of the matching Iris	mismatching	lower efficiency	x				Tuning	± 0.001 mm	high	local	2
LONGITUDINAL											
Expansion due to heat dissipation	dephasing	lower efficiency				x	Thermal elongation compensated (isotropic)	± 0.005 mm	low	thermal elongation	3
Tilt of the disks (Bookshelf)	transverse kick	RF induced transverse kick	x	x			Vertical V-block assembly	± 18 mrad **	high	bookshelf	4
TRANSVERSE											
Relative position of disks	wakefield	beam induced transverse kick	x	x			V-block assembly	± 0.005 mm **	low	alignment problem	6
Peak of magnetic field on surface	magnetic field *	local temperature rising	x	x			***	***	low	local	
Expansion due to unsymmetrical heat dissipation	wakefield	beam induced transverse kick				x	Symmetric deformation design	± 0.005 mm	high	bending	5
Thermal isotropic expansion	dephasing	lower efficiency				x	Very accurate water temperature control	± 0.1 °C	high	variation of the structures	10
Supporting of accelerating structure	wakefield	beam induced transverse kick	x	x	x		Accurate reference interfaces in structures	± 0.005 mm	low	structure axis wrt beam axis	9
TILT											
Tilt of the full structure	transverse kick	RF induced transverse kick			x		Reference points in the structures	± 0.03 mrad	low	tilt of full structure	7
Deformation of support	transverse kick	RF induced transverse kick				x	Active cooling system	± 0.03 mrad	low	support interference	8



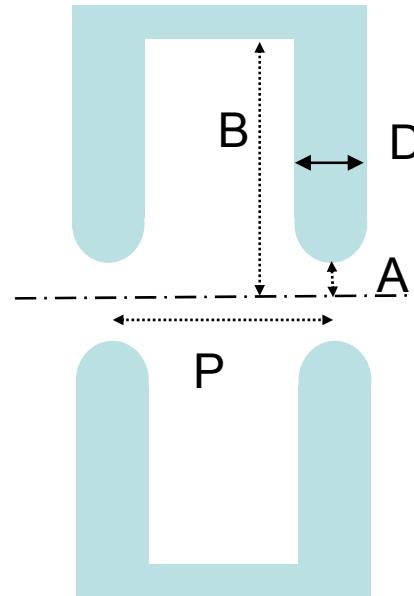
Structure Shape

Dephasing:

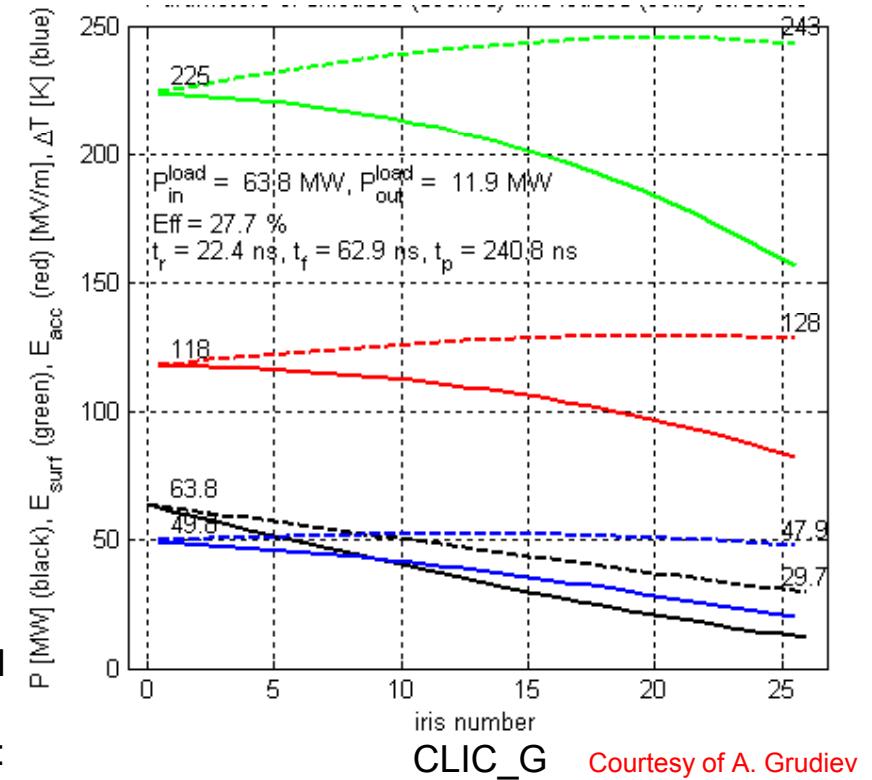
Beam dynamics: An error in the cell shape determines a wrong phase advance

Mismatching:

Reflected power: in a structure a geometrical error introduces a reflection i.e. lower efficiency. Considering the last cell (narrowband; $v_g=0.83\%$) , the pass band at -30 dB is ~5 MHz and the computed tolerance (dB) to get $S11 < -30$ dB is ~1.5 micron, if any tuning is applied.



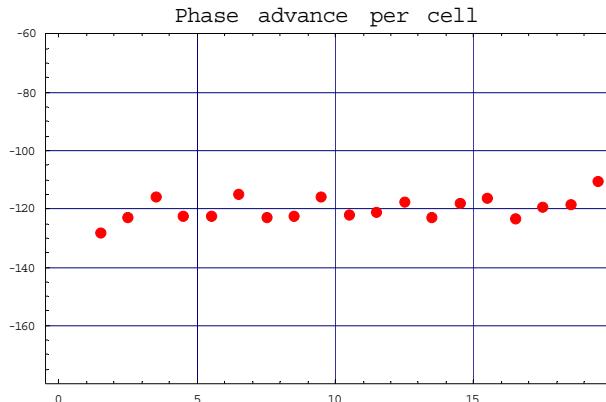
The sensitivity of the phase advance to the main geometrical parameters has been computed for the different cells of the CLIC_G structure. Strong dependence on the group velocity: $v_g/c(\%)$: 1.66 (first cell) 0.83 (last cell)



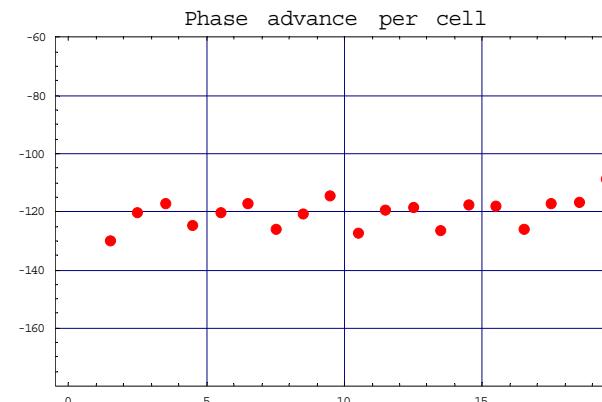
Courtesy of A. Grudiev

Example of errors: CLIC_VG1: RF measurements in KEK

Every error can distribution can be schematically considered as the sum of systematic errors plus random errors



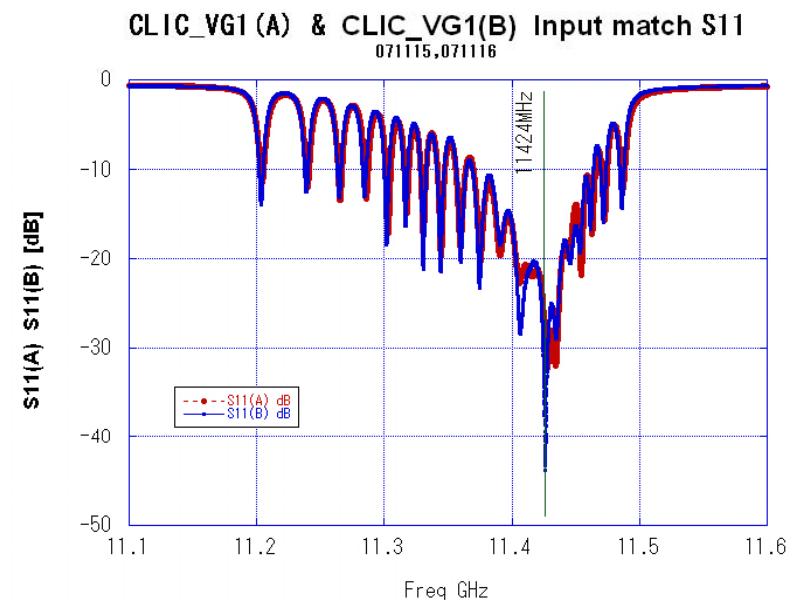
Average phase advance per cell
-119.943 degrees / cell



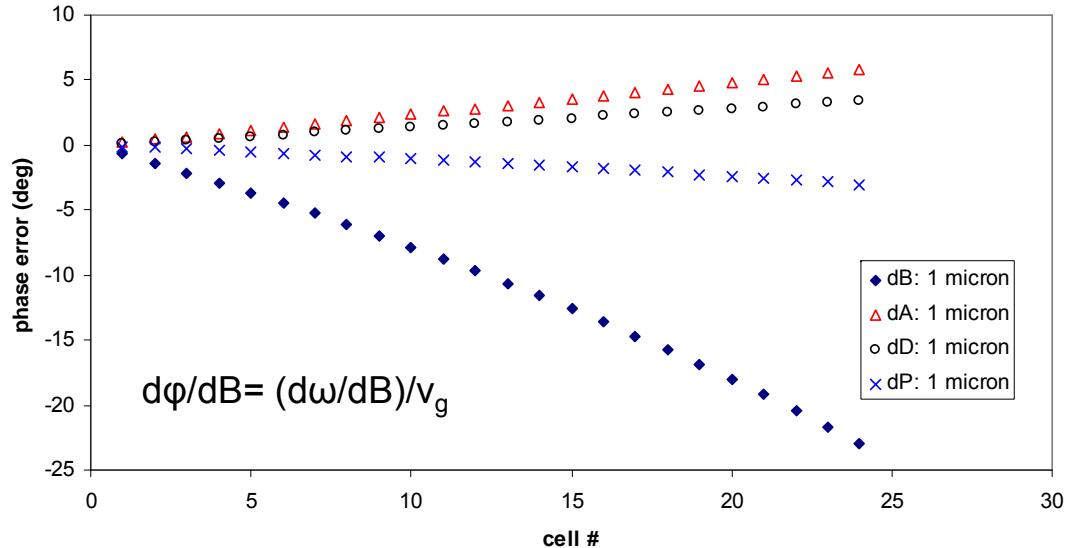
Average phase advance per cell
-120.424 degrees / cell

Single cell phase advance error up to 10 deg,
sigma A~ 4.5 deg, sigma B~ 5.6 deg

Courtesy of T. Higo



Structure Shape (systematic error)

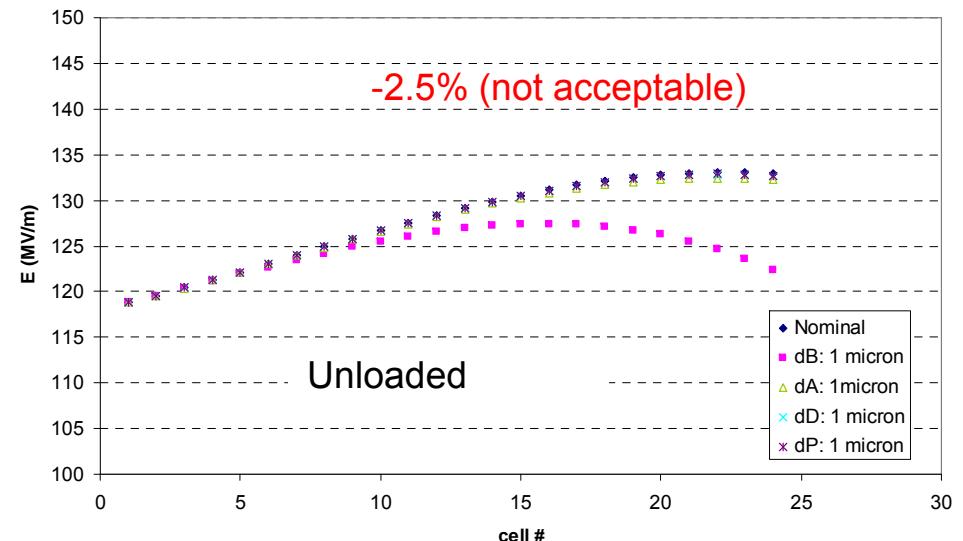
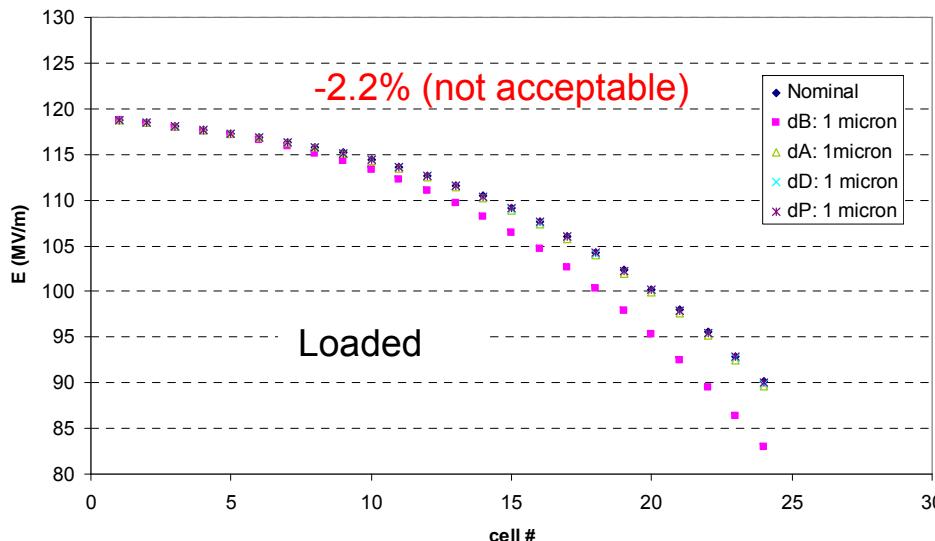


	df/dB (radius) [MHz/ μ m]	dph./df [deg/MHz]
cell1	1.1	0.6
cell24	1.0	1.2

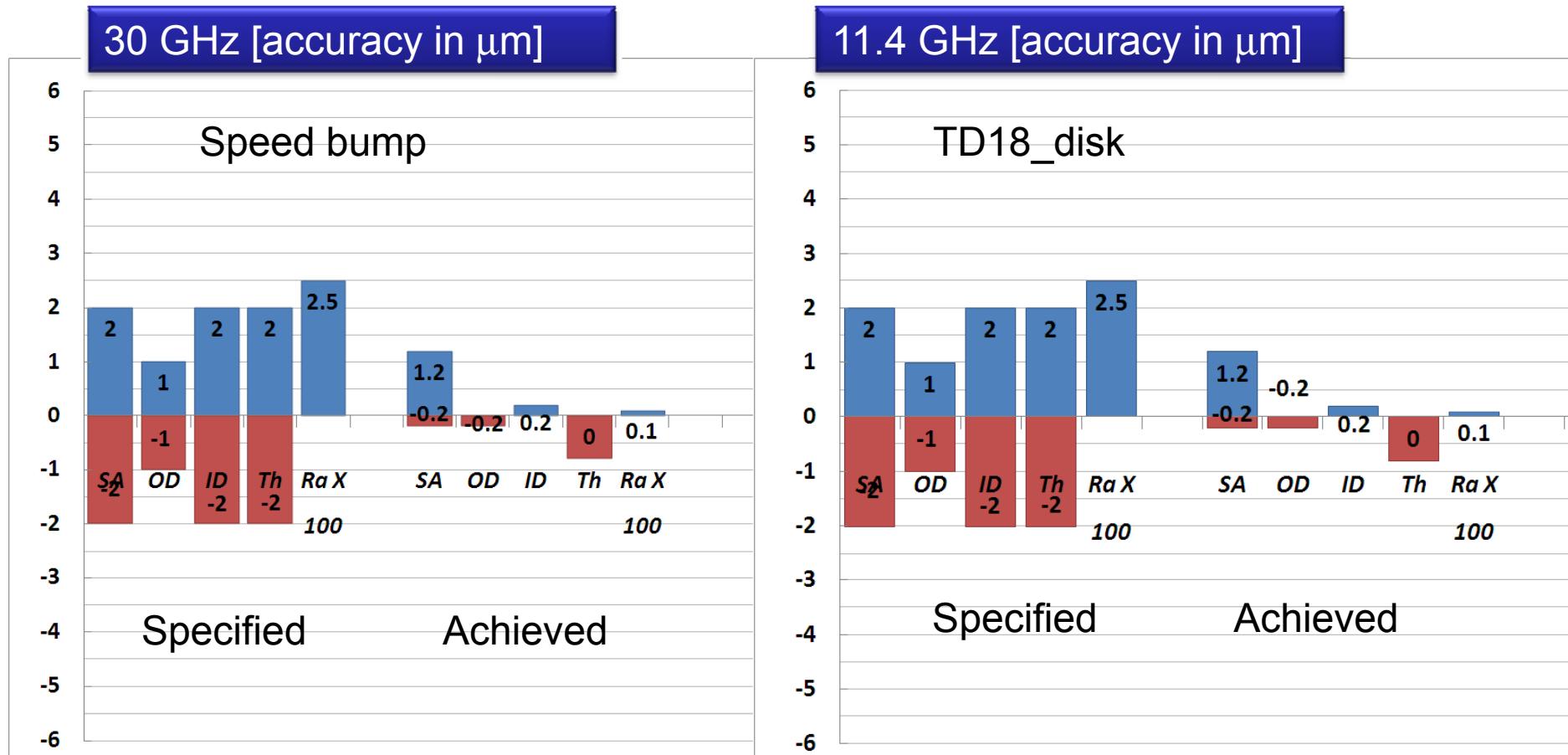
Cumulative error: 1 micron error, if systematic, gives a very large error on the average phase advance per cell (~ 11 deg cumulative phas. err.)



The phase error implies a variation on the effective accelerating field



Achieved accuracy (disk)



SA: iris shape accuracy

OD: outer diameter

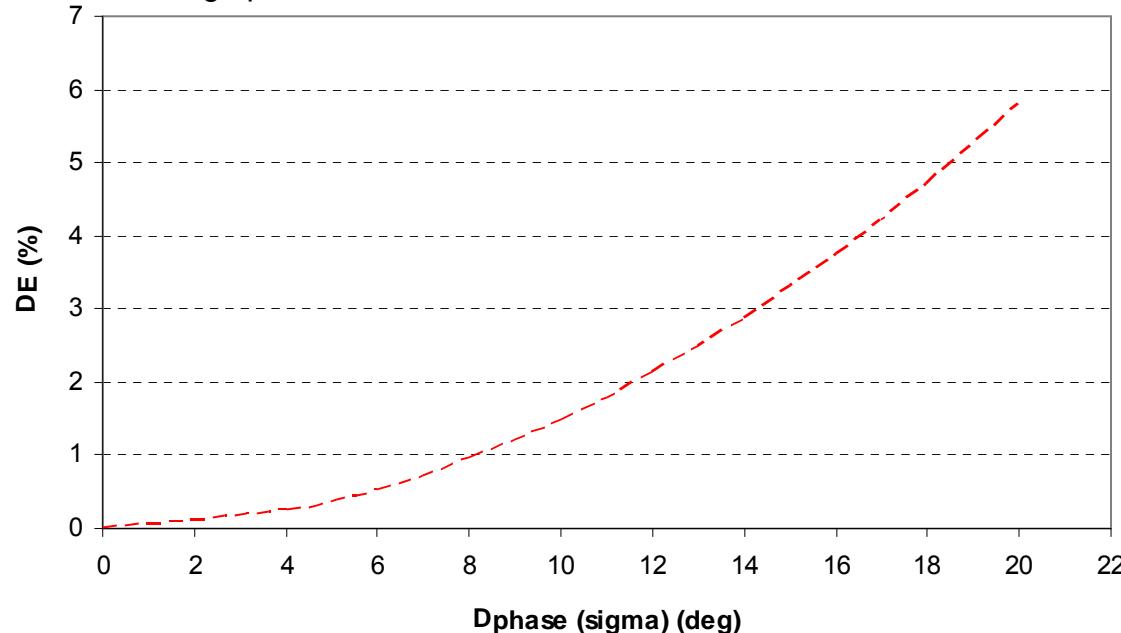
ID: inner diameter

Th: iris thickness

Ra: roughness

Structure Shape (random error)

Gradient error generated by a Gaussian distribution of the cumulative phase;
NO average phase error.

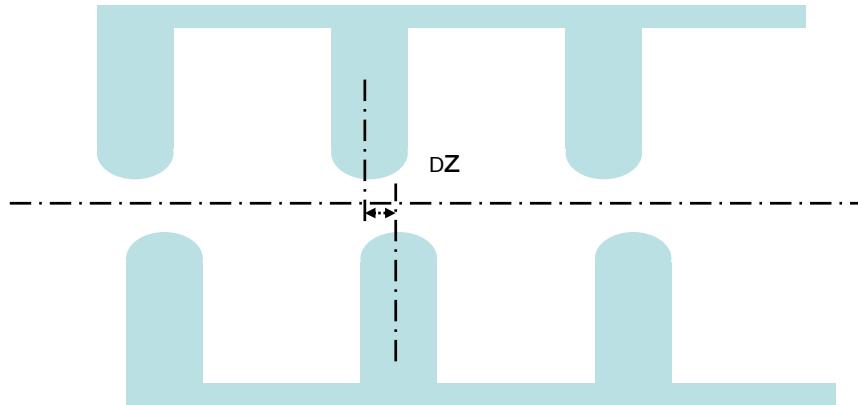


Acceptable average gradient error: sigma=2% (D. Schulte)

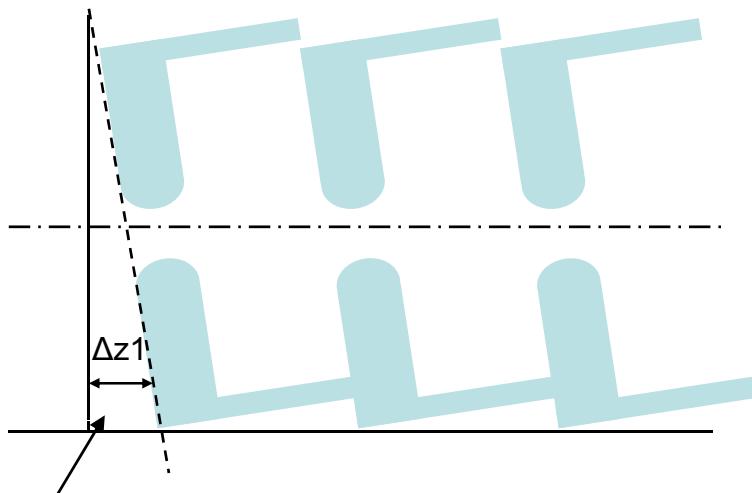


$\Delta B < 17$ microns (first cell); 9 microns (last cell)

Bookshelf or longitudinal misalignment of half-structure



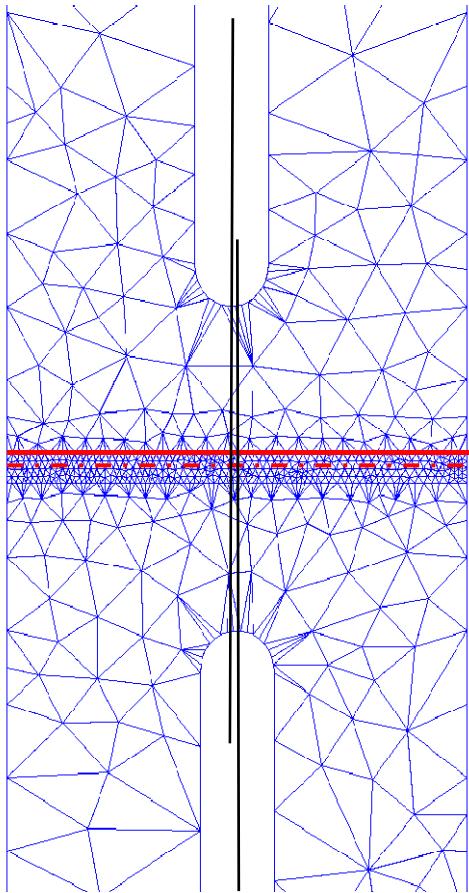
Structure in quadrants
problem mainly for the
machining and **assembly**



Structure in disks
problem mainly for the **brazing**
(assembly); probably easier to achieve

$$\Delta z_1 \approx D/a^* \Delta z$$

Bookshelf or longitudinal misalignment of half-structure

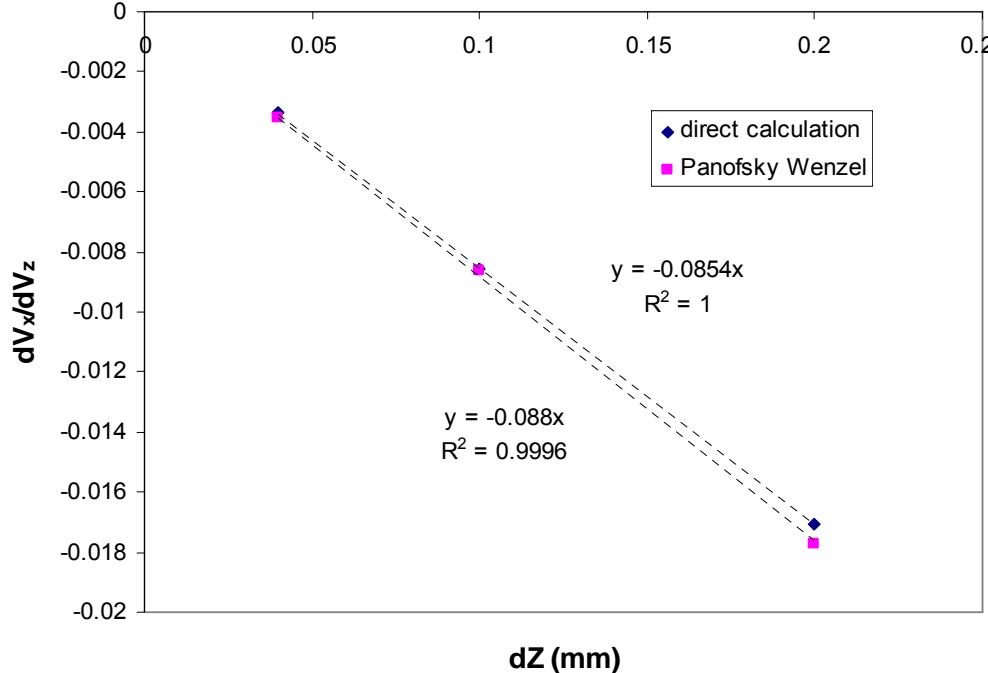


Middle cell of CLIC_G
($a=2.75\text{mm}$)

$$V_x := \int_0^{Z_{\text{end}}} [(E_x(z) - H_y(z)) \cdot \exp[i \cdot (\kappa \cdot z - \phi)]] dz$$

$$\Delta \vec{V}_\perp = i \frac{v}{m} \vec{\nabla}_\perp (\Delta V_\Pi)$$

Direct kick calculation
Panofsky Wenzel
(cross-check)



$dV_x/dV_z \sim 0.087 * dZ$
computed

$$dV_x/dV_z = dZ/(4*a) = 0.09 * dZ$$

Prediction (Daniel)

Equivalent bookshelf
angle: $\alpha = dZ/2a$

Tolerances: 1 micron or
 $180 \mu\text{rad}$

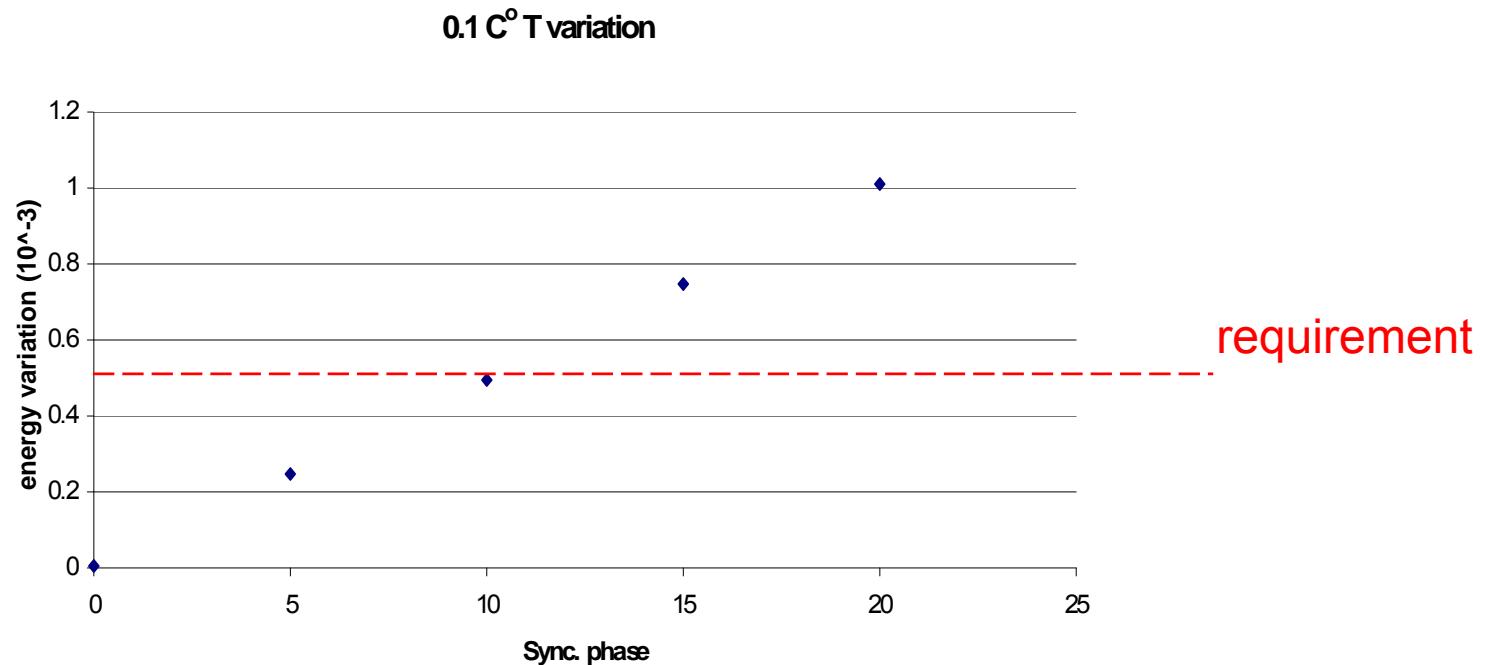
Thermal isotropic expansion

Assumption: isotropic dilatation for small variation of the temperature of the cooling water

Conservative approach: same T variation for the full linac (present design; one inlet for one linac)

Dilatation has two effects on phase:

- 1) Elongation of the structure; 1D problem, negligible effect
- 2) Detuning and consequent phase error of each cell; 3D problem, dominant effect



The average gradient variation is “equivalent” to 0.2 deg phase jitter(*) (drive beam-main beam phase)

(*) In the case of synchronous phase = 8 deg

Conclusions

- RF mismatching, phasing errors and bookshelf are critical for structure tolerances
- Bookshelf for structures in disks requires equivalent tolerances ($\sim 180 \mu\text{rad}$)
- Variation of the cooling water temperature could generate beam energy variations;
(feedback system ?)
- For a massive production we should avoid mechanical tuning (deformation); Can we partially compensate by changing slightly the absolute position of a module?

Thanks to: S. Barakou,j. Huopana, R. Nousiainen, D. Schulte,